

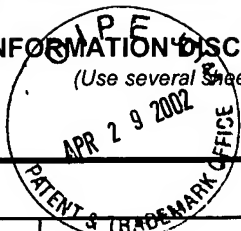


<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)				ATTY DOCKET NO. 2002U		SERIAL NO. NOT ASSIGNED	
				Joseph E. Oberlander et al			
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<b>U.S. PATENT DOCUMENTS</b>							
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RA		4,491,628	01/01/1985	Hiroshi Ito et al			
		4,521,274	06/04/1985	Elsa Reichmanis et al			
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		5,585,219	12/17/1996	Yuko Kaimoto et al			
RA		5,635,333	06/03/1997	John S. Peterson et al			
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
RA		EP 0 794,458		Europe			
		GB 2320718		Great Britain			
		EP 583,205		Europe			
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RA		GB 2135 793		Great Britain			
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RA		K. Bather et al, "TiN, O, As a Barrier Between Cr-Si(O) and Aluminum Thin Films", Thin Solid Films, 200 (1991) pg 93 - 117					
RA		C. Nolscher et al, "High contract single layer resists and antireflection layers - an alternative to multilayer resist techniques", SPIE Vol. 1086 Advances in Resist Technology and Processing VI (1989) pg 242 - 250					
EXAMINER R. Ashton				DATE CONSIDERED 7/15/03			

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	5,882,996	03/16/1999	Chang-Ming Dal			
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UA	F. M. Houlihan et al, "Chemically Amplified Resists: The Chemistry and Lithographic Characteristics of Nitrobenzyl Benzenesulfonate Derivatives", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 259 - 273

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RA		T. Yamaoka et al, "Photochemical Dissociation of p-Nitrobenzyl Aromatic Sulfonate and Its Application to Chemical Amplification Resists", Journal of Photopolymer Science and Technology, Volume 3, No. 3 (1990) pages 275 - 280
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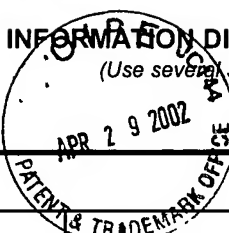
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RA		James Fahey et al, "Design of a Bottom Anti-Reflective Layer for Optical Lithography", SPIE, Vol. 2195, pages 422 - 2195

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